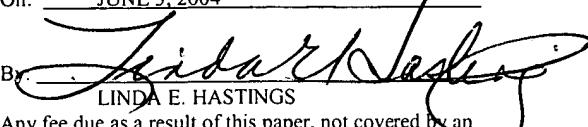




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Attorney Docket No.: NECF 17.638B (100806-00233)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: Mami MIYASAKA

Serial No.: 10/657,429

Confirmation No.: 9031

Filed: September 8, 2003

Title: **ELECTRON BEAM EXPOSURE MASK, ELECTRON BEAM
EXPOSURE METHOD, METHOD OF FABRICATING
SEMICONDUCTOR, AND ELECTRON BEAM EXPOSURE
APPARATUS**

Examiner: Anthony G. Quash

Group Art Unit: 2881

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT

SIR:

In response to the Office Action mailed on March 3, 2004, the period for responding thereto having been set to expire after June 3, 2004, please amend the subject application as follows: